

## Message Text

CONFIDENTIAL

PAGE 01      OECD P 33303 101424Z

47

ACTION EB-07

INFO OCT-01 CIAE-00 COME-00 DODE-00 NRC-05 NSAE-00 USIA-06

TRSE-00 EUR-12 ERDA-05 ISO-00 /036 W

----- 044798

R 101522Z NOV 76

FM USMISSION OECD PARIS

TO SECSTATE WASH DC 4192

C O N F I D E N T I A L OECD PARIS 33303

EXCON

E.O. 11652: XGDS1

TAGS: ESTC, COCOM, CZ, GW

SUBJECT: GERMAN MASK ALIGNMENT AND EXPOSURE

EQUIPMENT TO CZECHOSLOVAKIA--IL 1355

REF: (A) COCOM DOC (76) 1022, (B) STATE 171900

(C) COCOM DOC (76) 1679

1. DEPARTMENT'S ATTENTION IS DRAWN TO REFDOK C WHICH  
RESPONDS TO QUESTIONS REFTEL B.

2. REFDOK C EXPLAINS THAT NEED FOR SIMULTANEOUS EXPO-  
SURE IS JUSTIFIED AS MOST EFFICIENT WAY TO PRODUCE CER-  
TAIN SEMI-CONDUCTOR ELEMENTS. US VIEWS ON REF-  
CASE NOW REQUIRED NOVEMBER 17.

2. ACTION REQUESTED: US VIEWS BY NOVEMBER 17.  
TURNER

CONFIDENTIAL

NNN

## Message Attributes

**Automatic Decaptioning:** X  
**Capture Date:** 01 JAN 1994  
**Channel Indicators:** n/a  
**Current Classification:** UNCLASSIFIED  
**Concepts:** STRATEGIC TRADE CONTROLS, EXCEPTIONS LIST, SEMICONDUCTOR DEVICES  
**Control Number:** n/a  
**Copy:** SINGLE  
**Draft Date:** 10 NOV 1976  
**Decaption Date:** 01 JAN 1960  
**Decaption Note:**  
**Disposition Action:** RELEASED  
**Disposition Approved on Date:**  
**Disposition Authority:** buchant0  
**Disposition Case Number:** n/a  
**Disposition Comment:** 25 YEAR REVIEW  
**Disposition Date:** 28 MAY 2004  
**Disposition Event:**  
**Disposition History:** n/a  
**Disposition Reason:**  
**Disposition Remarks:**  
**Document Number:** 1976OECDP33303  
**Document Source:** CORE  
**Document Unique ID:** 00  
**Drafter:** n/a  
**Enclosure:** n/a  
**Executive Order:** X1  
**Errors:** N/A  
**Film Number:** D760419-0341  
**From:** OECD PARIS  
**Handling Restrictions:** n/a  
**Image Path:**  
**ISecure:** 1  
**Legacy Key:** link1976/newtext/t19761162/aaaacbvs.tel  
**Line Count:** 46  
**Locator:** TEXT ON-LINE, ON MICROFILM  
**Office:** ACTION EB  
**Original Classification:** CONFIDENTIAL  
**Original Handling Restrictions:** n/a  
**Original Previous Classification:** n/a  
**Original Previous Handling Restrictions:** n/a  
**Page Count:** 1  
**Previous Channel Indicators:** n/a  
**Previous Classification:** CONFIDENTIAL  
**Previous Handling Restrictions:** n/a  
**Reference:** 76 STATE 171900  
**Review Action:** RELEASED, APPROVED  
**Review Authority:** buchant0  
**Review Comment:** n/a  
**Review Content Flags:**  
**Review Date:** 27 APR 2004  
**Review Event:**  
**Review Exemptions:** n/a  
**Review History:** RELEASED <27 APR 2004 by hartledg>; APPROVED <08 NOV 2004 by buchant0>  
**Review Markings:**

Margaret P. Grafeld  
Declassified/Released  
US Department of State  
EO Systematic Review  
04 MAY 2006

**Review Media Identifier:**  
**Review Referrals:** n/a  
**Review Release Date:** n/a  
**Review Release Event:** n/a  
**Review Transfer Date:**  
**Review Withdrawn Fields:** n/a  
**Secure:** OPEN  
**Status:** NATIVE  
**Subject:** GERMAN MASK ALIGNMENT AND EXPOSURE EQUIPMENT TO CZECHOSLOVAKIA--IL 1355  
**TAGS:** ESTC, CZ, GE, COCOM  
**To:** STATE  
**Type:** TE  
**Markings:** Margaret P. Grafeld Declassified/Released US Department of State EO Systematic Review 04 MAY 2006